

**Amendments to the Specification:**

Please replace the paragraph beginning on line 12 of page 1 with the following amended paragraph:

There are number of different forms of differential confocal microscopy. In one differential form, the Nomarski microscope measures one component of a conjugated quadratures of fields corresponding to the electrical interference signal of two images superimposed in an image plane. In another differential form, the conjugated quadratures of a dark field are measured one point at a time. In another differential form, the conjugated quadratures of each of two fields corresponding to two images superimposed in an image plane are measured one point at a time. In commonly owned U.S. Provisional Patent Application No. 60/447,254 (ZI-40) entitled "Transverse Differential Interferometric Confocal Microscopy" and U.S. Patent Application No. [[\_\_\_\_\_]] 10/778,371, filed Feb. 13, 2004 (ZI-40) also entitled "Transverse Differential Interferometric Confocal Microscopy" both of which are by Henry A. Hill, it is taught how to practice transverse differential interferometric confocal microscopy. In commonly owned U.S. Provisional Patent Application No. 60/448,360 (ZI-41) entitled "Longitudinal Differential Interferometric Confocal Microscopy" and U.S. Patent Application No. [[\_\_\_\_\_]] 10/782,057, filed Feb. 19, 2004 (ZI-41) also entitled Longitudinal Differential Interferometric Confocal Microscopy" both of which are by Henry A. Hill, it is taught how to practice longitudinal differential interferometric confocal microscopy. The contents of both the cited U.S. Provisional Applications and the cited U.S. Patent Applications are herein incorporated in their entirety by reference.

Please replace the paragraph beginning on line 4 of page 23 with the following amended paragraph:

Referring to the bi-homodyne detection method, a set of four electrical interference signal values are obtained for each pair of spots in or on substrate **60** being imaged such as described in commonly owned U.S. Provisional Patent Application No. 60/442,858 (ZI-47) and entitled

"Apparatus and Method for Joint Measurements of Conjugated Quadratures of Fields of Reflected/Scattered Beams by an Object in Interferometry" and U.S. Patent Application 10/765,369, filed Jan. [[\_\_\_\_]] 27, 2004 (ZI-47) and entitled "Apparatus and Method for Joint Measurements of Conjugated Quadratures of Fields of Reflected/Scattered and Transmitted Beams by an Object in Interferometry" both of which are by Henry A. Hill. The contents of both the cited U.S. Provisional Patent Application and the U.S. Patent Application are herein incorporated in their entirety by reference. The set of four electrical interference signal values  $S_j$ ,  $j = 1, 2, 3, 4$  used for obtaining conjugated quadratures of fields for a single a spot on and/or in a substrate being imaged is represented for the bi-homodyne detection within a scale factor by the formula

$$S_j = P_j \left\{ \begin{array}{l} \xi_j^2 |A_1|^2 + \zeta_j^2 |B_1|^2 + \eta_j^2 |C_1|^2 + \zeta_j \eta_j 2 |B_1| |C_1| \cos \varphi_{B_1 C_1} \varepsilon_j \\ + \xi_j \zeta_j 2 |A_1| |B_1| \cos \varphi_{A_1 B_1} \varepsilon_j + \varepsilon_j \xi_j \eta_j 2 |A_1| |C_1| \cos \varphi_{A_1 C_1} \\ + \xi_j^2 |A_2|^2 + \zeta_j^2 |B_2|^2 + \eta_j^2 |C_2|^2 + \zeta_j \eta_j 2 |B_2| |C_2| \cos \varphi_{B_2 C_2} \gamma_j \\ + \xi_j \zeta_j 2 |A_2| |B_2| \cos \varphi_{A_2 B_2} \gamma_j + \gamma_j \xi_j \eta_j 2 |A_2| |C_2| \cos \varphi_{A_2 C_2} \end{array} \right\} \quad (1)$$

where coefficients  $A_1$  and  $A_2$  represent the amplitudes of the reference beams corresponding to the first and second frequency components of the input beam; coefficients  $B_1$  and  $B_2$  represent the amplitudes of background beams corresponding to reference beams  $A_1$  and  $A_2$ , respectively; coefficients  $C_1$  and  $C_2$  represent the amplitudes of the return measurement beams corresponding to reference beams  $A_1$  and  $A_2$ , respectively;  $P_j$  represents the integrated intensity of the first frequency component of the input beam in pulse  $j$  of the pulse sequence; and the values for  $\varepsilon_j$  and  $\gamma_j$  are listed in Table 1. The change in the values of  $\varepsilon_j$  and  $\gamma_j$  from 1 to -1 or from -1 to 1 correspond to changes in relative phases of respective reference and measurement beams. The coefficients  $\xi_j$ ,  $\zeta_j$ , and  $\eta_j$  represent effects of variations in properties of a conjugate set of four pinholes such as size and shape used in the generation of the spot on and/or in substrate **60** and the sensitivities of a conjugate set of four detector pixels

corresponding to the spot on and/or in substrate **60** for the reference beam, the background beam, and the return measurement beam, respectively. [[.]]

Please replace the paragraph beginning on line 12 of page 43 with the following amended paragraph:

A first embodiment comprises the interferometer system of Figs. **1a-1c** with interferometer **10** of the first embodiment that is shown schematically in Fig. **2a**. Interferometer **10** comprises an interferometer such as described in commonly owned U.S. Provisional Patent Application filed No. 60/447,254 (ZI-40) entitled "Transverse Differential Interferometric Confocal Microscopy" and U.S Patent Application 10/778,371, filed February 13, 2004 (ZI-40) also entitled "Transverse Differential Interferometric Confocal Microscopy" both of which are by Henry A. Hill. The contents of the U.S. Provisional Patent Application and the U.S. Patent Application are herein incorporated in their entirety by reference.

Please replace the paragraph beginning on line 21 of page 43 with the following amended paragraph:

Interferometer **10** of the first embodiment comprises a first imaging system generally indicated as numeral **110**, pinhole array beam-splitter **112**, detector **70**, and a second imaging system generally indicated as numeral **210**. The second imaging system **210** is low power microscope having a large working distance, *e.g.* Nikon ELWD and SLWD objectives and Olympus LWD, ULWD, and ELWD objectives. The first imaging system **110** comprises an interferometric confocal microscopy system described in part in commonly owned U.S. Provisional Application No. 60/442,982 (ZI-45) entitled "Interferometric Confocal Microscopy Incorporating Pinhole Array Beam-Splitter" and U.S. Patent Application No. [[      ]] 10/765,229, filed January 27, 2004 (ZI-45) and also entitled "Interferometric Confocal Microscopy Incorporating Pinhole Array Beam-Splitter" both of which are by Henry A. Hill. The contents of both of the U.S. Provisional

Patent Application and the U.S. Patent Application are herein incorporated in their entirety by reference.

Please replace the paragraph beginning on line 1 of page 57 with the following amended paragraph:

The throughputs of the first embodiment can be further increased by the use of a pinhole array beam-splitter that is coupled to input beam **24** by a guided-wave structure such as described in commonly owned U.S. Provisional Patent Application No. 60/445,739 (ZI-39) entitled "Multiple-Source Arrays Fed By Guided Wave Structures And Resonant Structures For Confocal And Near-Field Confocal Microscopy" and U.S. Patent Application No. [[\_\_\_\_\_]] 10/744,250, filed February 6, 2004 (ZI-39) and also entitled "Multiple-Source Arrays Fed By Guided Wave Structures And Resonant Structures For Confocal And Near-Field Confocal Microscopy" both of which are by Henry A. Hill. The contents of the cited U.S. Provisional Patent Application and the U.S. Patent Application are incorporated herein in their entirety by reference.

Please replace the paragraph beginning on line 10 of page 58 with the following amended paragraph:

The first and second embodiments may also be configured for quad-homodyne detection such as described herein and in cited U.S. Provisional Patent Application No. 60/442,858 (ZI-47) and cited U.S. Patent Application 10/765,369, filed Jan. 27, 2004 (ZI-47) entitled "Apparatus and Method for Joint Measurements of Conjugated Quadratures of Fields of Reflected/Scattered Beams by an Object in Interferometry" (ZI-47).

Please replace the paragraph beginning on line 26 of page 60 with the following amended paragraph:

In certain end use applications, the interior of substrate **60** is imaged. In this case, there will be aberrations introduced. In another embodiment, compensation for aberrations is

accomplished by introducing a thin layer (the thin layer has an index of refraction different from lens **150**) between lens **150** and pinhole array beam-splitter **112** such as described in commonly owned U.S. Provisional Application No.. 60/444,707(ZI-44) entitled "Compensation of Effects of Mismatch in Indices of Refraction At a Substrate-Medium Interface in Confocal and Interferometric Confocal Microscopy" and U.S. Patent Application No. [[\_\_\_\_\_]] 10/771,785, filed February 4, 2004 (ZI-44) and also entitled "Compensation for Effects of Mismatch in Indices of Refraction at a Substrate-Medium Interface in Confocal and Interferometric Confocal Microscopy" both of which are by Henry A. Hill. The contents of the U.S. Provisional Patent Application and the U.S. Patent Application are incorporated herein in ~~there~~ their entirety by reference.

Please replace the paragraph beginning on line 26 of page 62 with the following amended paragraph:

Other embodiments may use the quad-homodyne detection method instead of the bi-homodyne detection method as variants of the embodiments. For the embodiments that are based on the apparatus shown in Figs. **1a-1c**, the corresponding variants of the embodiments that use the quad-homodyne detection method use variants of the apparatus shown in Figs. **1a-1c**. In the variants of the apparatus such as used in the first embodiment, microscope **220** is modified to include a dispersive element such as a direct vision prism and/or a dichroic beam-splitter. When configured with a dichroic beam-splitter, a second detector is further added to the system. Descriptions of the variants of the apparatus are the same as corresponding portions of descriptions given for corresponding systems in cited U.S. Provisional Application No. 60/442,982 (ZL45) and U.S. Patent Application No. [[\_\_\_\_\_]] 10/765,229, filed January 27, 2004 (ZI-45) entitled "Interferometric Confocal Microscopy Incorporating Pinhole Array Beam-Splitter".